# **Characterization of silicon nitride single crystals and pOlycrystalline reaction sintered silicon nitride by microhardness measurements**

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Identification of  $\alpha$ - and  $\beta$ -phases of  $Si_3N_4$  single crystals grown from Si melt could be made with the help of Vickers microhardness measurements. The effect of chemical additives, e.g. metallic Fe and BaF<sub>2</sub>, on the microhardness of  $Si_3N_4$  was also determined. Different constants involved in the empirical Meyer relationship between load and indentation diameters could be correlated with the porosity and microhardness of  $Si<sub>3</sub>N<sub>4</sub>$ single crystals and polycrystalline, reaction sintered Si<sub>3</sub>N<sub>4</sub>.

## 1. **Introduction**

For a long time microhardness measurements have been frequently utilized to characterize silicon nitride  $[1-4]$ . Parr *et al.*  $[1]$  investigated the effect of nitridation of silicon at various temperatures and characterized the resulting silicon nitride by microhardness measurements. Pratt [2] reported that the  $\alpha$ - and  $\beta$ -phases of reaction sintered silicon nitride can also be distinguished by their microhardness properties, and in fact,  $\alpha$ -Si<sub>3</sub>N<sub>4</sub> was found to be harder than  $\beta$ -Si<sub>3</sub>N<sub>4</sub> in the polycrystalline matte. But Noakes and Pratt [4] later reported that both the  $\alpha$ - and  $\beta$ -phases of polycrystalline  $Si_3N_4$  have identical Vickers microhardness values. Coe *et al.* [5] reported that an inverse relationship exists between hardness and strength of hot-pressed  $Si<sub>3</sub>N<sub>4</sub>$ . They further reported that an inverse relationship also exists between hardness and grain size of  $Si<sub>3</sub>N<sub>4</sub>$ . Niihara and Hirai [6] studied the microhardness anisotropy in different crystallographic faces of  $\alpha$ -Si<sub>3</sub>N<sub>4</sub> single crystals grown by the chemical vapour deposition (CVD) method. Hardness and wear behaviour of  $Si_3N_4$  ceramics, with special reference to surface deformation behaviour, have been studied by Page *etal.* [7].

In the present paper an attempt has been made to identify  $\alpha$ - and  $\beta$ -phases of Si<sub>3</sub>N<sub>4</sub> single crystals grown from melt with the help of Vickers microhardness measurements. In addition, an attempt has been made to correlate the constants involved in the empirical relationship between load and indentation diameter with the porosity and microhardness of  $Si<sub>3</sub>N<sub>4</sub>$  single crystals and polycrystalline  $Si<sub>3</sub>N<sub>4</sub>$ . The empirical relationship was first described by Meyer [8].

# **2. Experimental procedure**

# 2.1. Preparation of  $Si<sub>3</sub>N<sub>4</sub>$

 $\beta$ -Si<sub>3</sub>N<sub>4</sub> single crystals (of size  $\sim$  60  $\mu$ m || *c*-axis and  $\sim 30 \,\mu\text{m} \perp c$ -axis) were grown at 1450°C from silicon melt (of purity 99.99%) and specially pure nitrogen, with or without 0.1 wt% and 1.0 wt % Fe. Details of the experimental procedures have been reported elsewhere [9].  $\alpha$ -Si<sub>3</sub>N<sub>4</sub> single crystals could be grown along with  $\beta$ -Si<sub>3</sub>N<sub>4</sub> single crystals provided that the silicon melt contained **1.0 wt %** Fe.

Polycrystalline  $\alpha$ -Si<sub>3</sub>N<sub>4</sub> was made by nitriding commercial silicon (particle size  $\leq$  200 mesh) at 1350°C, while  $\alpha + \beta$ -Si<sub>3</sub>N<sub>4</sub> were made together by nitriding silicon first at  $1350^{\circ}$ C and then at 1450 $^{\circ}$  C [10, 11]. Prior to nitriding the silicon bars were pressed either uniaxially  $[2 \text{ tsi } (3.09 \times$  $10^7 \text{ N m}^{-2}$  or 8 tsi  $(1.24 \times 10^8 \text{ N m}^{-2})$  or isostatically  $[16 \text{ tsi } (2.47 \times 10^8 \text{ N m}^{-2})]$ . Most of the

polycrystalline  $Si<sub>3</sub>N<sub>4</sub>$  samples were fully converted during the nitriding process but only a few had unconverted silicon in  $Si_3N_4$ . The  $\alpha$ - and  $\beta$ -phases of  $Si<sub>3</sub>N<sub>4</sub>$  were identified by X-ray analysis.

## 2.2. Measurement of microhardness

Small samples of  $Si<sub>3</sub>N<sub>4</sub>$  were mounted in resin, ground and finally polished with diamond paste. The Vickers microhardness was measured with a Leitz Miniload Hardness Tester. Care was taken to make indentation only on that region of polycrystalline  $Si<sub>3</sub>N<sub>4</sub>$  which had minimum number of visible pores. For the  $Si<sub>3</sub>N<sub>4</sub>$  having unconverted silicon, indentation was made on a region free from unconverted silicon.

Microhardness measurements in order to identify the microhardness anisotropy could not be made on individual crystallographic faces because of the small sizes of single crystals. Therefore, the reported microhardness values should be considered as the average of values for different crystallographic faces.

## **2.3. Determination of porosity**

The porosity of polycrystalline  $Si<sub>3</sub>N<sub>4</sub>$  was measured using an Hg-porosimeter. The porosity of single crystals was assumed to be zero.

## **3. Results and discussion**

Table I lists sample nature, indentation diameter and Vickers microhardness at loads of 100g, 200 g, 300 g and 500 g, for  $\alpha$ - and  $\beta$ -Si<sub>3</sub>N<sub>4</sub> single crystals with or without Fe-additive, and  $\alpha$ - and  $\alpha + \beta$ -polycrystalline Si<sub>3</sub>N<sub>4</sub> with or without BaF<sub>2</sub>additive.  $Si<sub>3</sub>N<sub>4</sub>$  single crystals, polycrystalline  $Si<sub>3</sub>N<sub>4</sub>$  and  $Si<sub>3</sub>N<sub>4</sub>$  having unconverted silicon have been designated by SC, PC and UN respectively. The porosities of samples were found to be **as**  follows: Samples  $1-6$ , 0%; Samples  $7-9$ , 12%; Sample 10, 18.5%; Samples 11-15, 25%; Samples 16-17, 27%. Each indentation diameter is the average of 15 observations. Standard deviation in per cent for indentation diameters have been indicated in parenthesis. The ratio of minimum to maximum loads, used for making the indentations, was kept at 1:5 following the suggestion of Dunegan [3] that it should be kept within 1:10. Loads lesser than 100 g were not used to avoid error in measurement due to the smallness of the resulting indentation diameter. Loads larger than 500g were not used to avoid cracking around indentation. Table I shows that the Vickers microhardness (VMH) decreases with increasing load for  $Si<sub>3</sub>N<sub>4</sub>$  single crystals and polycrystalline  $Si<sub>3</sub>N<sub>4</sub>$  as expected for hard and brittle ceramic materials [3,4].

## 3.1. Identification of  $\alpha$ - and  $\beta$ -Si<sub>3</sub>N<sub>4</sub> **single** crystals

The  $\alpha$ - and  $\beta$ -phases of  $Si_3N_4$  have a light grey and deep grey colour respectively [3 ], and consequently the two phases could be distinguished and the indentation could be made selectively on either of the two phases of  $Si<sub>3</sub>N<sub>4</sub>$ . Samples 1–3 show that  $\alpha$ -Si<sub>3</sub>N<sub>4</sub> single crystals have a higher VMH than  $\beta$ -Si<sub>3</sub>N<sub>4</sub>.

Fig. 1 shows a typical  $\alpha$ - and  $\beta$ -Si<sub>3</sub>N<sub>4</sub> single crystal with an indentation made at 100 g load. It can be easily seen that  $\alpha$ -Si<sub>3</sub>N<sub>4</sub> has smaller indentation diameter than  $\beta$ -Si<sub>3</sub>N<sub>4</sub> indicating that the former is harder than the latter. It may be pointed out that this difference in microhardness cannot be due to differences in crystallographic orientation since both of the single crystals have similar types of orientation, as is evident from Fig. 1. Samples 7 and 10 show that polycrystalline  $\alpha$ -Si<sub>3</sub>N<sub>4</sub> has a higher VMH than polycrystalline  $\alpha + \beta$ -Si<sub>3</sub>N<sub>4</sub> indicating that polycrystalline  $\alpha$ -Si<sub>3</sub>N<sub>4</sub> is harder than polycrystalline  $\beta$ -Si<sub>3</sub>N<sub>4</sub>. It may be noticed that Sample 10 has higher porosity than Sample 7. Present authors also performed VMH measurements on the  $\alpha$ - and  $\beta$ -phases of Si<sub>3</sub>N<sub>4</sub> in the two-stage polycrystalline samples, as performed by Pratt [4]. A consistent difference in the VMH for  $\alpha$ - and  $\beta$ -phases could not be achieved, however, because of the dissimilar distribution of pores in the  $\alpha$ - and  $\beta$ -phases. Because the  $\beta$ -phase is formed from the melt it normally has a lesser number of pores than the  $\alpha$ -phase. Hence, perhaps, the



*Figure 1* Optical micrograph of  $\alpha$ - and  $\beta$ -Si<sub>3</sub>N<sub>4</sub> single crystals with Viekers indentation at a load of 100g. Light colour:  $\alpha$ -Si<sub>3</sub>N<sub>4</sub>, deep colour:  $\beta$ -Si<sub>3</sub>N<sub>4</sub>, (× 280).





n.d.: not determined. n.d.: not determined.<br>F: BaF<sub>3</sub> .<br>\*Bracketed terms indicate standard deviation in %. \*Bracketed terms indicate standard deviation in %.



*Figure 2* Relation between the slope of the Meyer line, *n*, and porosity (%) of  $\text{Si}_3\text{N}_4$ .

increased VMH of  $\alpha$ -Si<sub>3</sub>N<sub>4</sub> has been accentuated in such samples by the comparatively higher porosity of that phase and, consequently, the VMH of  $\alpha$ -Si<sub>3</sub>N<sub>4</sub> has been found to be lower than that of  $\beta$ -Si<sub>3</sub>N<sub>4</sub>. The only value obtainable in the existing literature of the VMH of  $\alpha$ -Si<sub>3</sub>N<sub>4</sub> single crystals grown by the CVD method is  $3343 \text{ kg mm}^{-2}$ at load of 100 g, which is the average of the values for the three crystallographic faces [7]. This is somewhat low in comparison with the VMH values obtained in the present work.

It may be mentioned that  $\beta$ -Si<sub>3</sub>N<sub>4</sub> has a slightly higher density than  $\alpha$ -Si<sub>3</sub>N<sub>4</sub> [12]; in spite of this,  $\alpha$ -Si<sub>3</sub>N<sub>4</sub> has been found to be harder than  $\beta$ -Si<sub>3</sub>N<sub>4</sub>. This is contrary to the normal behaviour of ceramic materials.

#### 3.2. The effect of chemical additives on the hardness

Samples 2-6 show that  $\beta$ -Si<sub>3</sub>N<sub>4</sub> samples grown with no Fe-additive exhibit a higher VMH value than those with an Fe-additive. The reason for choosing an Fe-additive is that it enhances and favours the growth of  $\beta$ -Si<sub>3</sub>N<sub>4</sub> [13-15]. Samples 4-6 show that increase in the concentration of the Fe-additive from  $0.1$  wt% to  $1.0$  wt% does not further reduce the VMH values.

Samples 7–9 show that the addition of  $BaF<sub>2</sub>$ improves the VMH values of polycrystalline  $Si<sub>3</sub>N<sub>4</sub>$ .  $BaF<sub>2</sub>$  is added because it enhances the siliconnitrogen reaction [11,16]. Experience in this

laboratory has shown that isostatically pressed silicon bars which were not fully nitrided, even after prolonged heating above  $1420^{\circ}$  C, could become so if 1 wt %  $BaF<sub>2</sub>$  was added to the mixture. It was also observed that the percentage of  $\alpha$ -phase in  $BaF_2$ -containing polycrystalline  $Si_3N_4$  was higher. Low temperature  $(<1420^{\circ}$  C) nitridation product of powdered silicon containing BaF<sub>2</sub> yielded more than 90 wt % of the  $\alpha$ -phase. Addition of  $BaF<sub>2</sub>$  improves the VMH, probably due to an enhanced percentage of the  $\alpha$ -phase being present in polycrystalline  $Si<sub>3</sub>N<sub>4</sub>$ .

Samples 7-8 and 16-17 show that unconverted silicon present in  $Si<sub>3</sub>N<sub>4</sub>$  does not deteriorate the VHM of  $Si<sub>3</sub>N<sub>4</sub>$ .

# 3.3. Dependence of slope and intercept of Meyer line on porosity and microhardness

The Meyer line is defined by the linear relationship

$$
\log P = n \log d + \log a, \tag{1}
$$

where  $P$  is the load,  $d$  is the indentation diameter,  $n$  is a constant that is the slope of the Meyer line and a is a constant. Meyer lines were drawn for the loads and indentation diameters listed in Table I. Thus *n* and  $log a$  could be found out from the slope and intercept of the Meyer line, respectively.

Plotting of the slope of the Meyer line,  $n$ , against porosity shows that  $n$  linearly decreases with increasing porosity (see Fig. 2). Hence, some estimation of the porosity of  $Si<sub>3</sub>N<sub>4</sub>$  can be made from the slope of the Meyer line. This is an important observation because, until now, the slope of the Meyer line was not known to have any correlation with any physical property of  $Si<sub>3</sub>N<sub>4</sub>$ .

Vickers microhardness at a load of 100g,  $VMH<sub>100</sub>$ , is plotted against porosity in Fig. 3. In spite of the large scatter in  $VMH_{100}$  it can be observed that VMH<sub>100</sub> for  $Si<sub>3</sub>N<sub>4</sub>$  single crystals is higher than that of polycrystalline  $Si<sub>3</sub>N<sub>4</sub>$ , as expected. Moreover,  $VMH_{100}$  to some extent linearly decreased with porosity. The large scatter in  $VMH_{100}$  is due to the difference in VMH for the two phases  $\alpha$  and  $\beta$  of  $Si_3N_4$  and to the deterioration of VMH as a result of the influence of the Feadditive (see Section 3.1).

Comparison of Figs 2 and 3 indicates that the scatter in data points in Fig. 2 is less than that in Fig. 3. Hence it can be pointed out that the slope of the Meyer line,  $n$ , can give a better indication of porosity of  $Si<sub>3</sub>N<sub>4</sub>$  than the individual VMH



*Figure 3* Relation between the Vickers microhardness at a load of  $100 g$  (VMH<sub>100</sub>) and porosity (%) of  $Si_1N_a$ .

value. This is so because the influence of the nature of the phase of  $Si<sub>3</sub>N<sub>4</sub>$  and of the chemical additive is much more prominent in the VMH values than it is in the slope of the Meyer line.

Fig. 4 shows that slope of Meyer line,  $n$ , increases non-linearly with increasing  $VMH_{100}$  and, hence, *n* can given an indication of microhardness. A few values of VMH<sub>100</sub> and corresponding *n* values from the existing literature  $[2, 6]$  have been introduced in Fig. 4. These data points from literature fit reasonably well within the present figure.

Fig. 5 depicts the intercept of the Meyer line,  $(\log a)$ , against VMH<sub>100</sub>. It is observed that  $\log a$ increases non-linearly with  $VMH_{100}$  and hence some evaluation of the VMH of  $Si<sub>3</sub>N<sub>4</sub>$  can be made from the  $\log a$  value.

It is observed from Table I that the standard deviation of the indentation diameters for the polycrystalline  $Si<sub>3</sub>N<sub>4</sub>$  are on average two times larger than those for  $Si_3N_4$  single crystals. This



*Figure 4* Relation between the slope of the Meyer line,  $n<sub>1</sub>$  and the Vickers microhardness at a load of 100 g  $(VMH<sub>100</sub>)$ .



*Figure 5* Relation between the intercept of the Meyer line (log a) and the Vickers microhardness at a load of  $100 g$  (VMH<sub>100</sub>).

deafly indicates that the indentation diameters are influenced by the different sizes of pores in polycrystalline  $Si<sub>3</sub>N<sub>4</sub>$ .

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